

REMARKS

Claims 36-54 are pending in this application.

With respect to applicants claim for priority, the present application is a National phase application for PCT/SE02/01179 which claims priority to Swedish application No. 0102144-3 filed June 15, 2001. Each page of the filed application is stamped with PCT/SE02/01197 and the unexecuted declaration filed with the application correctly identifies the application as being originally filed under the Patent Cooperation Treaty with International Application No. PCT/SE02/01197. Finally, the executed declaration also correctly identifies the application as being originally filed under the Patent Cooperation Treaty with International Application No. PCT/SE02/01197.

Claims 36-40, 43, 48, 49 and 54 stand rejected under 35 U.S.C 102(b) as being anticipated by U.S. Patent No. 6,475,369 to Cohen. In addition, claims 41 and 42 stand rejected under 35 U.S.C, 103(a) as being unpatentable over Cohen in view of U.S. Patent No 4,279,709 to McIntyre et al. Claims 44-47 stand rejected under 35 U.S.C, 103(a) as being unpatentable over Cohen in view of U.S. Patent No. 6,036,833 to Tang et al. Claims 50, 51 and 53 stand rejected under 35 U.S.C, 103(a) as being unpatentable over Cohen in view of U.S. Patent No. 5,196,109 to Scott. Finally, claim 52 stands rejected under 35 U.S.C, 103(a) as being unpatentable over Cohen in view of U.S. Patent No. 4,932,518 to Bernards et al. These rejections are respectfully traversed.

Independent claim 36 recites an electrochemical pattern replication method for production of micro- or nano- structures of an electrically conductive material on a substrate. Claim 35 specifically recites, among other features, a master electrode 8 with an insulating pattern layer 3.

Cohen discloses an electroplating method. In the Office Action, it is alleged that Cohen discloses a “master electrode” 4a as illustrated in Fig. 11b. This assertion is incorrect.

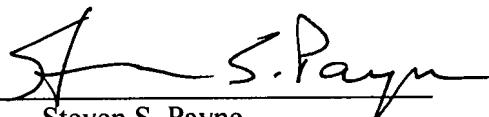
In Cohen, the first article 4a is comprised of a support 8 with a mask 6. As illustrated in Fig. 11b, the first article 4a is situated between the electrodes 2 and 10. In the present invention as recited in claim 36, the mask (insulating pattern layer) is located on the master electrode. This is completely different from Cohen wherein the mask is located on the support 8 located between the two electrodes. Thus, Cohen does not disclose a master electrode with an insulating pattern layer as is recited in independent claim 36. Thus independent claim 36 is not anticipated by Cohen.

With respect to the dependent claims 37-54, it is respectfully submitted that McIntyre et al., Tang et al., Scott and Bernards et al also do not disclose a master electrode as recited in independent claim 36. As a result, claims 37-54 are allowable over the cited prior art for at least the reasons set forth above with respect to claim 36.

In view of the above, it is respectfully submitted that the application is now in condition for allowance. Prompt notice of same is earnestly solicited. If the Examiner believes that a telephone interview may expedite the prosecution of the Application, the Examiner is invited to contact the below attorney at the indicated telephone number.

Respectfully submitted,

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